

ASM LPCVD Tube 2



Facts

- The ASM LPCVD is a two tube systems capable of depositing polysilicon, silicon nitride and LTO.
 - It is configured for both 4 inch and 6 inch wafers.
 - It uses dedicated quartz boats.
- Tube 2 - LPCVD of Silicon Nitride / Polysilicon
 - [Dichlorosilane](#) and [Ammonia](#) are brought into a heated furnace tube at low pressures to react and grow a silicon nitride film
 - [Silane](#) is brought into a heated furnace tube at low pressures to react and grow a poly silicon
- Other Tubes
 - [ASM LPCVD Tube 1 - LPCVD of low temperature oxide](#)

Personnel

- Tool Engineer - [Bruce Tolleson](#)
- Process Engineer - [Sean O'Brien](#)

Tool & Process Information

- [610C Poly Recipe](#)
- [650C Poly Recipe](#)
- [800C Sto Nitride Recipe](#)
- [810C Factory Nitride Recipe](#)

Manuals & Users

- [ASM LPCVD Manual](#)
- [ASM LPCVD Certification Checklist](#)